

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Bohumil Lojek

PATENT APPLICATION

Serial No.: 10/773,059

Group Art Unit: 2818

Filed: February 4 , 2004

Examiner:

For:

NON-VOLATILE MEMORY ARRAY WITH SIMULTANEOUS

WRITE AND ERASE FEATURE

## Supplemental Information Disclosure Statement

Hon. Commissioner for Patents Alexandria, VA 22313

Sir:

The following information is submitted in compliance with Applicant's duty of disclosure under 37 CFR § 1.56. A copy of the reference is enclosed.

## Other Reference

B. Eitan et al. (School of Applied Science and Technology, The Hebrew University of Jerusalem, Jerusalem, Israel), Impact Ionization at Very Low Voltages in Silicon, J. Appl. Phys. 53(2), February 1982, pp. 1244-1247.

This statement is believed to be filed before the mailing date of a first Office action on the merits. Applicant respectfully requests consideration by the PTO of the submitted information.

CERTIFICATE OF MAILING

I hereby certify that this paper (along with any paper referred to as being attached or enclosed) is being deposited with the United States Postal Service on the date shown below with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450

stelly anguedo Signed:

Typed Name: Sally Azevedo

Date: May 20, 2004

Respectfully submitted,

Thomas Schneck Reg. No. 24,518

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Sheet 1 of 3

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| U.S. PATENT DOCUMENTS  |    |   |                              |         |  |                  |                  |             |              |                |
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| FOREIGN PATENT DOCUMENTS   |    |   |                              |         |  |                  |                  |             |              |                |
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| OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) |    |   |                              |         |  |                  |                  |             |              |                |
|  | AO | B. Eitan et al. (School of Applied Science and Technology, The Hebrew University of Jerusalem, Jerusalem, Israel), Impact Ionization at Very Low Voltages in Silicon, J. Appl. Phys. 53(2), February 1982, pp. 1244-1247. |                              |         |  |                  |                  |             |              |                |
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\*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.